"Nano Mushroom"

Description:

This nano mushroom formed due to selfmasking during cryogenic etching of silicon. The nonmushroom part of the image is black silicon.

200 nm

Submitted by: Randy FechnerInAffiliation: Karlsruhe Institute of TechnologyN

Instrument: Zeiss Supra60VP Magnification: 15000 X

"The Micro Scrolls"

Description: A 100nm thick Nilayer detached from the surface during an HF bath, rolled up and stayed inside the cavities.

Submitted by: Randy FechnerInstAffiliation: Karlsruhe Institute of TechnologyMag

2 µm

2

Instrument: Zeiss Supra60VP Magnification: 2310 X



Description: This cigar-shaped pillar formed due to self-masking during cryogenic etching of silicon. The upper part is SiO₂ and the rest is Si.

1 µm

Submitted by: Randy Fechner Affiliation: Karlsruhe Institute of Technology

3

Instrument: Zeiss Supra60VP Magnification: 4460 X

"Balancing Nano Cube" Description:

This nano cube formed due to selfmasking during cryogenic etching of silicon and subsequent Nievaporation. The upper part is SiO₂ with some Ni on top. The rest is Si.

200 nm

Submitted by: Randy Fechner Affiliation: Karlsruhe Institute of Technology

4

Instrument: Zeiss Supra60VP Magnification: 17020 X

5 "Nanowires in love1"



Silicon nanowires pillar etched with SiO₂ capping layer on top. Nanowires bent during the XSEM inspection due to charging. Silicon pillar length is 275nm and SiO₂ cap of \varnothing 30nm.

20	mag 👳	HV	WD	
XS.	200 000 x	5.00 kV	2.5 mm	

Submitted by: BT. Chan / E. Camerotto Affiliation: imec / LAM

300 nm S54C

> Instrument: Hitachi Magnification: 200,000 X

6 "Nanowires in love2"



Silicon nanowires pillar etched with SiO₂ capping layer on top. Nanowires bent during the XSEM inspection due to charging. Silicon pillar length is 275nm and SiO₂ cap of \varnothing 30nm.

20	mag 👳	HV	WD	
XS.	200 000 x	5.00 kV	2.5 mm	

Submitted by: BT. Chan / E. Camerotto Affiliation: imec / LAM

300 nm S54C

> Instrument: Hitachi Magnification: 200,000 X

"Canada Heron"

Description:

Portrait of an ancient heron made of HSQ residues. The picture of this legendary bird was captured just after an electrolithography season.

Submitted by: Bruno LEE SANGInstrument: Zeiss – LEO 1540XBAffiliation: Interdisciplinary Institute for Technological Innovation,
SherbrookeMagnification: 167 X

"Apocalyptic Rat"

Description:

Warning! A dark matter, probably glue residues, in the form of a micrometric rat is having a bite of the corner of my delicious silicium sample.

Submitted by: Bruno LEE SANGInstrument: Zeiss – LEO 1540XBAffiliation: Interdisciplinary Institute for Technological Innovation,SherbrookeMagnification: 7.04 KX

1 um

"Portal to NanoWorld"

Description:

Silicon metal assisted chemical etching combined with Iridium atomic layer deposition. Resulting nanowires made of silicon organized themselves in a door like structure.

Submitted by: Joan Vila-Comamala Affiliation: ETH Zurich

9

Instrument: SEM Zeiss Supra VP55 Magnification: 50.00 kX

"SiliconCity Skyline"

Description:

Silicon reactive ion etching using a faulty Chromium mask.

2 µm

Mag = 9.00 K X WD = 3.5 mm

EHT = 5.00 kV Signal A = InLens Stage at T = 0.0 °

10

Date :1 Jun 2016 Time :19:46:20

Submitted by: Joan Vila-Comamala Affiliation: ETH Zurich

Instrument: SEM Zeiss Supra VP55 Magnification: 9.00 kX

10 um

"Silicon Shard Horse"

Description:

Silicon shards from a broken grating fabricated by deep reactive ion etching resemble a horse.

Submitted by: Joan Vila-Comamala Affiliation: ETH Zurich

11

Instrument: SEM Zeiss Supra VP55 Magnification: 4.5 kX

"Infinite Laberinth"

Description:

Silicon metal assisted chemical etching using a thin porous Gold layer.

200 nm

Mag = 100.00 K X WD = 3.7 mm

 $EHT = 5.00 \, kV$

Signal A = InLens

Stage at T = 0.0 °

Date :16 Dec 2015 Time :18:39:28

12

Submitted by: Joan Vila-Comamala Affiliation: ETH Zurich

Instrument: SEM Zeiss Supra VP55 Magnification: 100.00 kX



Description:

Silicon metal assisted chemical etching using a thin square of Gold that broke into pieces.

2 µm

Mag = 6.00 K X WD = 4.5 mm

Signal A = InLens

EHT = 5.00 kV

Tilt Angle = 0.0 °

13

Date :16 Nov 2015 Time :14:10:28

Submitted by: Joan Vila-Comamala Affiliation: ETH Zurich

Instrument: SEM Zeiss Supra VP55 Magnification: 6.00 kX

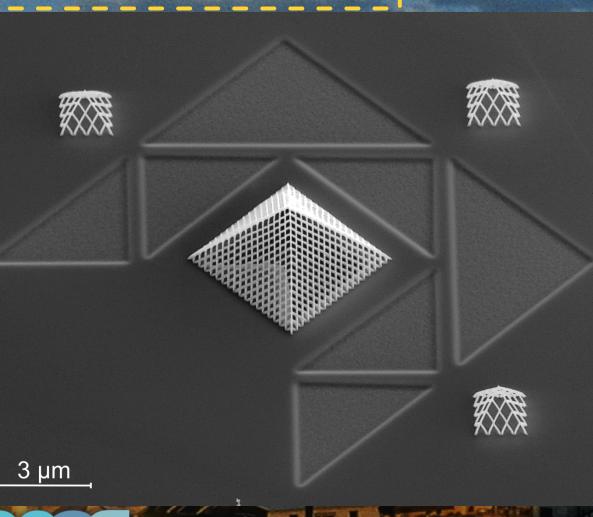
"Rapunzel, Rapunzel! Let down your hair!"

Medieval tower fabricated via Focused Electron Beam Induced Deposition (FEBID). This 3D-nanoprinted artificial lattice consists of platinum/carbon branches with individual diameter between 25-70 nm.

det HFW curr mag HV WD TLD 6.29 µm 0.40 nA 15 500 x 5.00 kV 4.9 mm _____2 μm _____ artificial PtC-Lattice 14

Submitted by: Robert WinklerInstrument: FEI Fib Nova200Affiliation: ZFE, Graz Centre for Electron MicroscopyMagnification: 15.5KX





"Nano-Louvre"

Replica of the glass pyramids in the courtyard of the Louvre (Paris) in a scale of 1: 8.000.000. The basement and the fountains are a FIB-cut, the 3Dstructures (branch sizes between 25 and 70 nm) consist of platinum and carbon. This image demonstrates the 3D-Nanoprinting capabilities of **Focused Electron Beam** Induced Deposition (FEBID) Compare it to the real OUV

Submitted by: Robert WinklerInstrument: FEI Fib Nova200Affiliation: ZFE, Graz Centre for Electron MicroscopyMagnification: 5KX



Description: The football-shaped nano particles were discovered on a small insect of leafhopper. Therefore, I don't know the origin, material and properties. These have a frame structure with a diameter of about 300 nm. Could you make a micro football field for bacteria?

120312 - 5KV X30.0K 1.00um

Submitted by: Hayato SoneInstrument: Hitach, S-900Affiliation: Gunma University (Gunma, Japan)Magnification: 30 kX

"Lotus fireplugs"

Description:

Mimicking Lotus leaf to produce silicon micro candles using photolithography and ICP-DRIE for superoleophobic surfaces.

10µm

Submitted by: (Sasha Hoshian) Affiliation: (Aalto University in Finland)

17

Instrument: Zeiss Supra 35 Magnification: 4000 X



Description:

Black silicon structures (Bosch process) as Microasparagus field, ready for harvesting with micro-harvester. Bon Appetite!

Submitted by: Katarzyna Korwin-Mikke Instrument: Zeiss Gemini Supra 25 **Affiliation: Oxford Instruments**

18

Magnification: 4.0kX

"Don't jump!"

Description:

Piece of peeled off resist mask - found this little fellow at the edge of deep silicon etch structures. Make sure you got the parachute before jump!

Submitted by: Katarzyna Korwin-MikkeInstrument: Zeiss Gemini Supra 25Affiliation: Oxford InstrumentsMagnification: 1.6kX

"Letter e"

Description:

Resist peeled off from the sample surface formed in letter e -There must be hidden message somewhere from micro-world.

Submitted by: Katarzyna Korwin-MikkeInstrument: Zeiss Gemini Supra25Affiliation: Oxford InstrumentsMagnification: 1.3kX

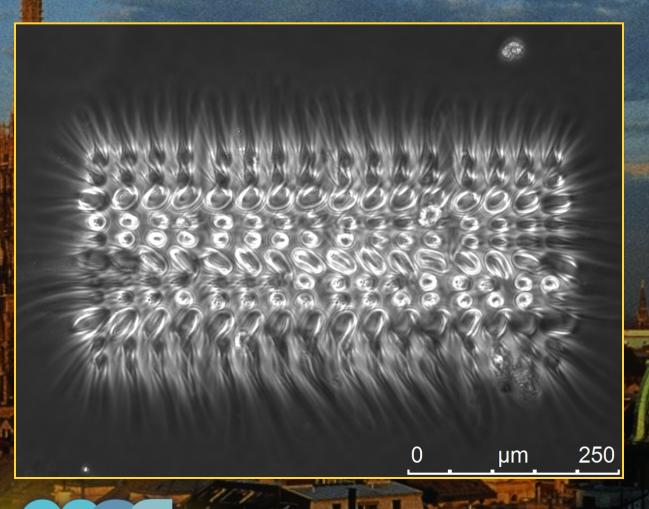
"Snail in cap"

Description:

Resist particles on the surface after cleaving the sample. The message received from the sample process as slow as snail. Snail in a fancy apple cap was pretty blind when I found him... I've given him possibility of admiring the beauty of microworld by adding antennae in Paint.

Submitted by: Katarzyna Korwin-MikkeInstrument: Zeiss Gemini Supra25Affiliation: Oxford InstrumentsMagnification: 4.6kX



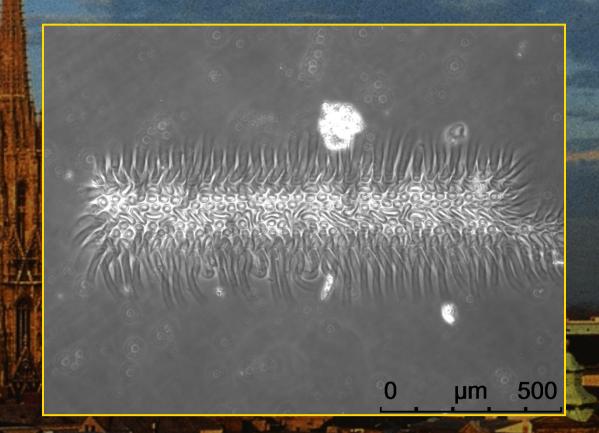


22

Description: Array of high aspectratio cylindrical shells made of gelatin hydrogel, fabricated by two photon lithography. Hydrated structures bend like long hollow chive leaves.

Submitted by: Laura BRIGO Instrument: DMI6000 B, Leica Microsystems Inc. Affiliation: University Of Padova Magnification: 40x objective (see scalebar)





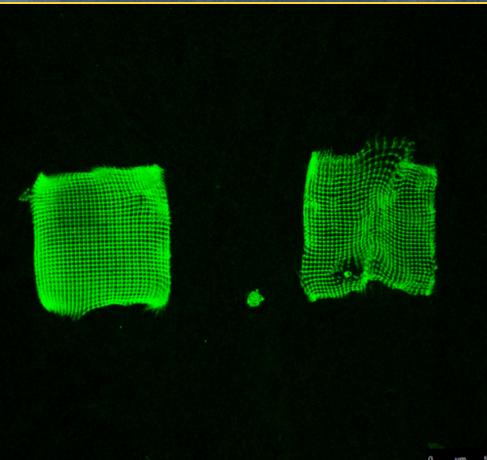
23

Description:

High aspect-ratio cylindrical shells made of gelatin hydrogel arranged in a long dense array, fabricated by two photon lithography, immersed in water.

Submitted by: Laura BRIGO Instrument: DMI6000 B, Leica Microsystems Inc. Affiliation: University Of Padova Magnification: 20x objective (see scalebar)





Description: Net structures made of hydrated gelatin hydrogel, fabricated by two photon lithography. The 3D nets are pulled and occasionally torn apart by cells invading them.

24

Submitted by: Laura BRIGO Instrument: Leica TCS SP5 confocal microscope Affiliation: University Of Padova Magnification: 40x objective (see scalebar)

"Martian Iceberg"

Description:

Silicon particle with carbon rich resist coating. Charging effects made it hard to get a sharp image but the effect is quite eerie.

Submitted by: Martin Spieser Affiliation: SwissLitho AG

25

Instrument: Zeiss LEO1550 SEM Magnification: 20 KX

1 µm

"Micro Lion"

Description:

This nice structure crystallized after development on the edge of a Fresnel zone plate made from HSQ.

Submitted by: Felix Marschall Affiliation: Paul Scherrer Institut

26

Instrument: SEM Zeiss Supra 55VR Magnification: 44000 X

"Cracking iron"

Description:

The ion image shows the cross section of an iron sample that was heavily bent until it cracked. The resulting crack and also the crystalline structure of the iron can be seen. The crack changes large crystalline structures to very small clusters near the crack.

HV	curr	dwell	det	mode	WD	tilt	mag 🎛	HFW	2 μm
30.00 kV	24 pA	10 µs	ETD	SE	13.0 mm	0 °	22 681 x	9.14 µm	TU Kaiserslautern NSC T. Loeber

Submitted by: Thomas LoeberInstrument: FEI Helios NanoLab 650Affiliation: NSC, TU KaiserslauternMagnification: 22.7 kX

dwell

100 ns

curr

0.10 nA

ΗV

2.00 kV

det

ETD

mode

SE

WD

3.9 mm 52 °

tilt

"Sticking out from the crowd"

Description:

The image shows a grid consisting of photoresist pillars and bars, which was written with the 3D laser lithography system Nanoscribe. A 40 nm thick titanium dioxide (TiO2) layer was deposited by atomic layer deposition on top of the structures. The pillar in the middle was milled with a FIB for analysis. It was verified that the structure was conformally covered with TiO2.

Submitted by: Thomas Loeber

mag 🎛

1 500 x

HFW

138 µm

28

Instrument: FEI Helios NanoLab 650 Magnification: 1.5 kX

30 um

TU Kaiserslautern NSC T. Loeber

"Frosty the SNOM snowman"

Description: The pyramidal tip of an AFM cantilever was partially cut off with a FIB system. In the truncated pyramid three glass spheres were stacked on top of each other. **A SNOM cantilever** with one glass sphere s used for diffuse light scattering. For fun the snowman was sketched.

curr 2.00 kV 0.10 nA 30 µs

X

WD det mode ETD SE

dwell

tilt mag 田 HFW 3.9 mm 52 ° 8 000 x 25.9 µm

5 um TU Kaiserslautern NSC T. Loeber

29

Submitted by: Thomas Loeber Affiliation: NSC, TU Kaiserslautern

Instrument: FEI Helios NanoLab 650 Magnification: 8.0 kX

"Animating a microbe"

Description:

The movie shows the reconstruction of a schmidingerothrix salinarum cell. The microbe was cut with a FIB. An image was taken from each slice. Over 500 images were aligned and the different elements of the cell were assigned to different colors. The cell outer membrane is shown in red, the cell nuclei are green and purple, the alveolar sheets are turquoise and bacteria inside the cell are yellow with a vacuole in blue.

Submitted by: Thomas LoeberInstrument: FEI Helios NanoLab 650Affiliation: NSC, TU KaiserslauternMagnification: kXSample provided by Lea Weinisch, Ecology Group, TU Kaiserslautern



Description:

Wind blows, grass grows. Those nanopillars with different orientation look like "Nano Grass".

Acc.V Spot Magn Det WD 10.0 kV 3.0 24956x SE 6.3

1 1 μm

31

Submitted by: ZHU ShuyanInstrument: Philips XL30 ESEMAffiliation: City University of Hong KongMagnification: 24956 X



Description: ZEP520A after eBeam exposure and development with overhanging residues due to insufficient rinsing.

Submitted by: Robert Kirchner Affiliation: Paul Scherrer Institut

32

Instrument: Zeiss Supra 55 VP Magnification: 47k X

2016 Micro-Nano Graph

"EAGLE"

Description: Dust particle on nano-imprinted polymer surface after Cr-coating (giving shadow effect)

Submitted by: Robert Kirchner Affiliation: Paul Scherrer Institut

33

Instrument: Zeiss Supra 55 VP Magnification: 19k X

Hexagon array around sucking loach lips

Description:

Confocal microscopy graph The sucking loach can attach to a stone or aquarium wall by its suckermouth. Around the suckermouth lips there is a sealing ring consists of hexagon array.

50um

34

Submitted by: Jinrong Wang Affiliation: Zhejiang Univ. Instrument: KEYENCE VK-X150 Magnification: 400 X

"Hexagonal Cone"

Description:

GaN is a wurtzite crystal with six-fold symmetry. Hexagonal cones can be etched by plasma etching method on GaN due to its anisotropy etch rate on different crystal faces, showing the symmetrical beauty of nature.

4/7/2013 WD ΗV HFW 4.0 mm 5.00 kV 6.40 µm 20 000 x 10:42:57 PM

mag 🎛 tilt 45 ° 2 µm Helios

35

Submitted by: Zhe Liu Instrument: FEI Helios 600i Affiliation: Institute of Physics, Chinese Academy of Sciences Magnification: 20 K X

"Construction Site"

Description:

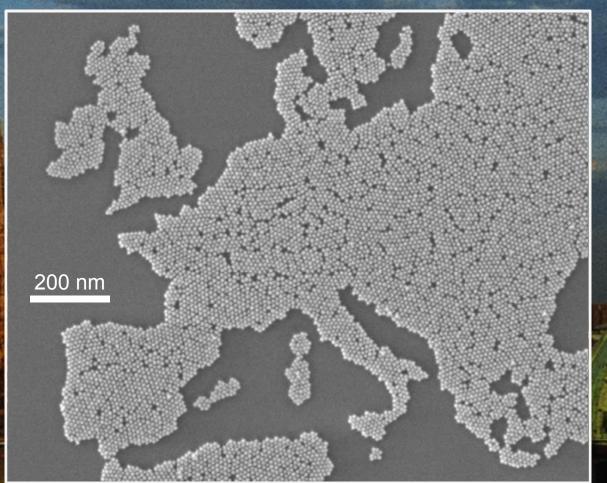
A construction site with 3D brackets regularly arranged in micro-scale, which were cut and folded by focused ion beam on suspended gold film.

5.00 kV SED 10.0 kX 52.0° 4.762 4	E-Beam		U U		FWD		-
	5.00 kV	SED	10.0 kX	52.0°	4.762	4	

10 µm

Submitted by: Zhe Liu Instrument: FEI DB235 Affiliation: Institute of Physics, Chinese Academy of Sciences Magnification: 10 K X

2016 Micro-Nano Graph



37

"The Spotted Continent"

Description: SEM image of a map of Europe consisting of a close packed monolayer of 10-nm gold nanoparticles, patterned by direct electron-beam exposure and subsequent emulsionbased development.

Submitted by: Patrick Reissner Affiliation: ETH Zürich Instrument: Hitachi SU8200 Magnification: 45 kX

"Secret Heaven"

Description:

Every single defect have its own mystery, this ITO coated glass defect have a secret heaven hidden.

Submitted by: Muhammed BEKINInstrument: FEI Nova NanoSEMAffiliation: Istanbul Technical UniversityMagnification: 30000 X

38

"Delicious Micro-(ca)rods"

Description:

single crystalline ZnO

Columnar,

delicious!

rods for novel

fingerprint sensor

imagine in orange

and green. Mmm,

technology. Just

SEM FIB Lock Mags = No

Mag = 38.03 K X WD = 7.8 mm EHT = 5.00 kV
 Signal A = SE2
 Date :22 Dec 2014

 Width = 9.939 μm
 Stage at Y = 39.462 mm

 Tilt Angle = 0.0 ° Off
 Stage at X = 64.173 mm



39

Submitted by: Christian Giese Affiliation: Fraunhofer IAF Instrument: Zeiss 15-40 EsB XB Magnification: 38 kX

"Micro-Mikado"

Description: Single crystalline ZnO micro-rods for fingerprint sensing. Note the nice twin specimen: X never ever marks the spot?

2 10/30/2015 WD mag HV Landing E → 10 μm 12:21:22 PM 6.7 mm 9 170 x 10.0 kV 10.0 keV vCD

> Submitted by: Christian Giese Affiliation: Fraunhofer IAF

40

Instrument: Hitachi S-4500 Magnification: 9 kX

"Micro Urchins"

Description:

Grown single crystalline ZnO rods for novel fingerprint sensor technology. Watch your (micro) step!

> Submitted by: Christian Giese Affiliation: Fraunhofer IAF

41

Instrument: Hitachi S-4500 Magnification: 25 kX

"Micro Smiley Community"

Description: Reactive ion etched

micropillars with wells of black silicon on top.

10 μm j

Mag = 2.88 K X Signal A = InLens Width = 96.00 μm EHT = 3.00 kV

InLens WD = 3.8 mm 0 kV Stage at T = 0.0 ° Time :15:43:15 Date :21 Apr 2016

42

Submitted by: Nikolaj K. Mandsberg Affiliation: DTU Nanotech Instrument: Zeiss Supra 40VP Magnification: 1062X

"Ah Hell, he's even more punk than me"

micro resist mag □ HV spot WD _____5 µm ____ technol gy 10 000 x 15.00 kV 2.5 10.3 mm OrmoStamp mit UV-PDMS gepraegt **Description:** Single OrmoStamp® pillar turned upside down and placed exactly at its ripp-off position by accident in an intact array of micro-pillars

Submitted by: Manuel ThesenInstrument: FEI InspectS50Affiliation: micro resist technology GmbHMagnification: 10.000 X

43

2016 Micro-Nano Graph

⁴⁴ "I worked my butt off for this nice SEM"

Description: Reflow of positive tone resist.

Submitted by: Arne Schleunitz & Susanne GruetznerInstrument: Fei InspectS50Affiliation: micro resist technology GmbHMagnification: 600 X

"Tender Embrace Flashmob"

> **Description:** Imprint of micro pillars in UV-curable hybrid polymer with PDMS stamp. Upon separation every second row bends forward to "hug" the opposite pillar.

Submitted by: Maria-Melanie Russew Affiliation: micro resist technology GmbH

45

Instrument: FEI InspectS50 Magnification: 3.000 2016 Micro-Nano Graph

"African ceremonial mask"

Positive structur lithogra African mask ar during

500 µm

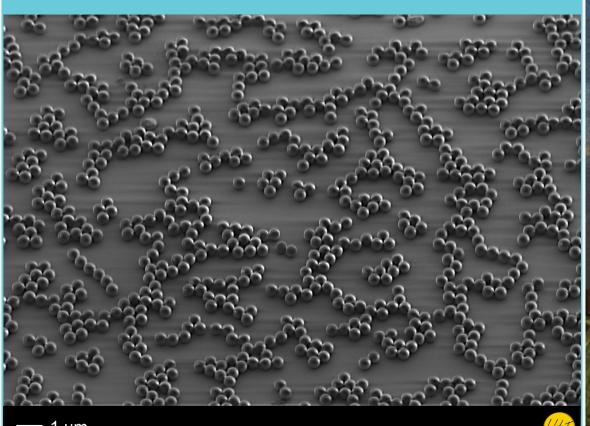
46

Description: Positive Tone Resist structured by UVlithography. The African ceremonial mask appeared during reflow.

Submitted by: Maria-Melanie Russew Affiliation: micro resist technology GmbH

Instrument: Olympus BX51M Magnification: 5x

"Nano marbles"



47

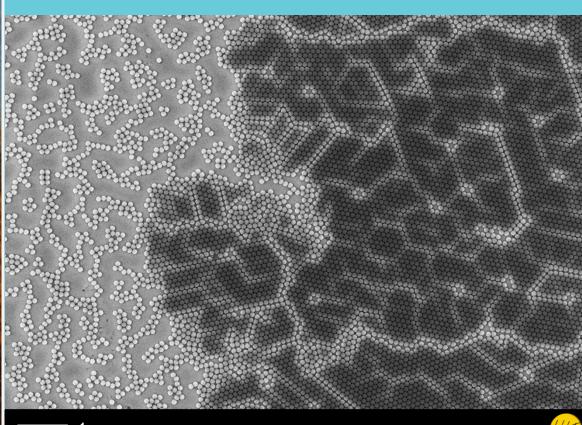
Description:

Tilted view of polystyrene particles prepared on silicon substrate as etch mask to fabricate silicon nanowires.

🗕 1 µm

Submitted by: Gerry Hamdana Affiliation: TU Braunschweig Instrument: SEM Zeiss Supra 35 Magnification: 5 KX

"Unfinished home"



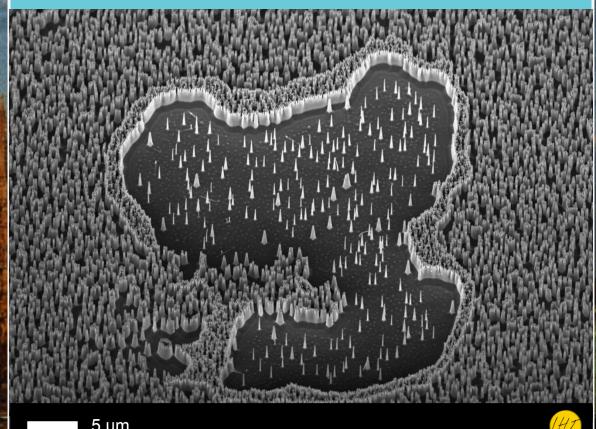
48

Description: Top view of transition zone between array and non-ordered polystyrene particles on silicon substrate. The particle arrays looked like honeycomb structures made by the bees.

1 µm

Submitted by: Gerry Hamdana Affiliation: TU Braunschweig Instrument: SEM Zeiss Supra 35 Magnification: 2 KX

"Within the walls"



49

Description:

Dry etch result of silicon nanowire by polystyrene particles as etch mask with different substrate coverage area. The fabricated nanowires were unevenly distributed on the sample.

5 µm



Instrument: SEM Zeiss Supra 35 **Magnification: 2 KX**

"Bird's eye view of the city"

Description:

Tilted view of silicon nanowire prepared by dry etching at cryogenic temperature. The structures were prepared by polystyrene particles as etch mask.

1 µm

Submitted by: Gerry Hamdana Affiliation: TU Braunschweig

50

Instrument: SEM Zeiss Supra 35 Magnification: 10 KX



Description: SU-8 layer was provided with a hole pattern by using nanoimprint. Following by an VUVtreatment (172 nm) before imprinting a line pattern in the surface near crosslinked SU-8. The hole pattern stays stable.

Acc.V Spot Magn Det WD Exp 2 μm 10.0 kV 2.0 12500x SE 5.8 0

> Submitted by: Christian Steinberg Affiliation: University of Wuppertal

51

Instrument: FEI XL 30S Magnification: 12500 X

Acc.V Spot Magn Det WD Exp 10.0 kV 2.0 6250x SE 13.4 0 "command in chief of the bugs army" **Description: SU-8** layer was provided with nano pillars by using nanoimprint. Following by an VUVtreatment (172 nm) before imprinting micro pillars in the surface near crosslinked SU-8. The cross-linked layer cracked so the micro pillars filled completely (middle).

Submitted by: Christian Steinberg Affiliation: University of Wuppertal

52

5 µm

Instrument: FEI XL 30S Magnification: 6250 X

"looking for the hidden treasure structures" Description:

> Replication of complex structures in UV-PDMS. The separation (PDMS/ master) of such structures is not so trivial. The master got stuck in the UV-PDMS. But fortunately we found some hidden complex structures.

Acc.V Spot Magn Det WD Exp 10.0 kV 2.0 6250x SE 5.1 0

53

Submitted by: Christian Steinberg Affiliation: University of Wuppertal Instrument: FEI XL 30S Magnification: 6250 X

⁵⁴ "No, it doesn't repeat"

\$#\$@\$#\$@\$#\$@\$#\$@\$#\$@\$#\$@\$#\$@\$#\$@\$#\$@ OHEOHEOHEOHEOHEOHEOHEOHEO $\mathbf{D}_{\mathbf{r}} \in \mathbf{O}_{\mathbf{r}} = \mathbf{O}_{\mathbf{r}} =$ 07+07+00+00+00+00+00+00+00+00 1 µm Mag = 10.00 K XSignal A = InLens WD = 4.6 mmDate :22 Aug 2016 $EHT = 6.00 \, kV$ Stage at T = 0.0 ° Stage at X = 65.988 mm Stage at Y = 44.352 mm Time :16:47:43

Description:

Quasi crystal structure with 12-fold rotational symmetry obtained with multiple-exposure Displacement Talbot Lithography

Submitted by: Christian Dais & Harun Solak Affiliation: EULITHA AG

Instrument: Make and Model

Magnification: 2500 X

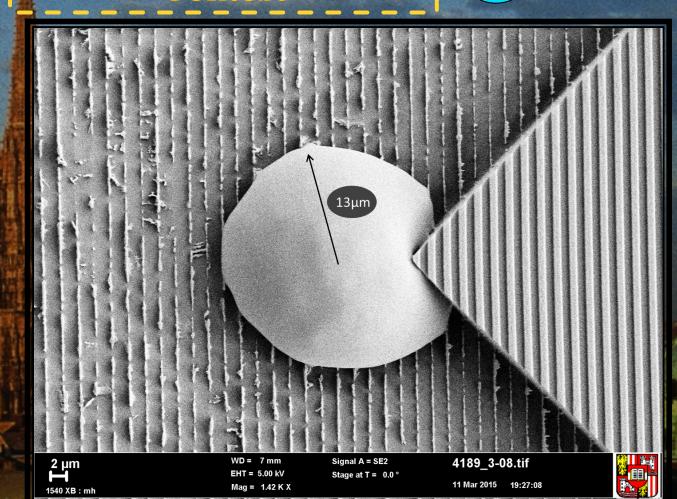


55

Description: Image shows a patterned curved surface fabricated with UV based soft nanoimprint lithography. The sphere has a diameter of around 100µm and the pillar pattern has a period of 2,5µm. The soft stamp deforms around the object and patterns the whole surface.

Submitted by: Michael J. Haslinger Affiliation: Profactor GmbH Instrument: ZEISS 1540XB CrossBeam Magnification: ??? X

"It's a packman"



56

Description: An important step in nanoimprint lithography an is the fabrication of copies of master stamp. The image shows an error in one copy step where an air inclusion occurred. Here the air inclusion is copied into a

imprint material.

Submitted by: Michael J. Haslinger Affiliation: Profactor GmbH Instrument: ZEISS 1540XB CrossBeam Magnification: 1.42 K X

"Sneezing Alien"



57

Description: This SEM image shows a defect in a metallic nanomesh produced with nano imprint lithography followed by a metal deposition and a wet chemical liftoff process. The upper layer of the metal/insulator/metal nanomesh is detached.

Submitted by: Michael J. Haslinger Affiliation: Profactor GmbH Instrument: ZEISS 1540XB CrossBeam Magnification:1.5 K X



58

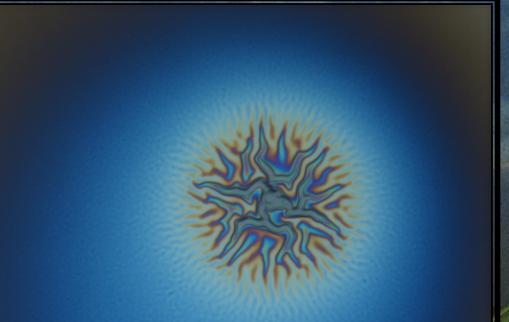
Description:

The optical microscope image shows scratches from a scalpel on a PMMA surface.

Affiliation: Profactor GmbH

Submitted by: Michael J. Haslinger Instrument : Nikon Eclipse LV150 mit DS-5M

59 "Exo-particle system"



Description: The optical microscope image shows some interesting capillary effects of a nanoimprint resist after spin coating on a Si-wafer.

Submitted by: Michael J. Haslinger Affiliation: Profactor GmbH

Instrument : Nikon Eclipse LV150 mit DS-5M

"spring board"

Description:

Bended spring board after a jump into a swimming pool

(PUA replica stamp with an air bubble)

Submitted by: Marc Papenheim Affiliation: University of Wuppertal

60

Instrument: FEI/Philips XL 30S FEG Magnification: 10KX

"Nails anyone?"

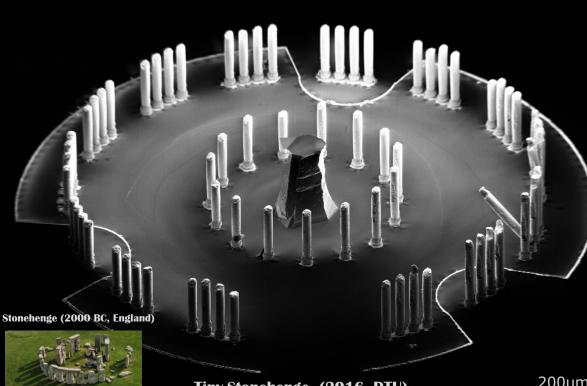
Description: Ever had need for nails for assembling you own microhouse? Look no further! Silicon micronails available now in your local micro-DIY store!

Submitted by: Ville Rontu Affiliation: Aalto University

61

Instrument: Zeiss Supra 40 Magnification: 522 X

"Tiny-Stonehenge"



62

Description:

The skeleton of copper pillars. After electroplating, silicon substrate is removed leaving the copperfilled through-silicon vias.



Tiny-Stonehenge (2016, DTU)

200µm

Instrument: ZEISS Supra 40VP SEM Submitted by: Hoa Thanh le Affiliation: Technical University of Denmark Magnification: ??? X

"LAByrinth"

Description: It's a 3D pyrolyzed carbon LAByrinth ©

Submitted by: Suhith Hemanth Affiliation: DTU, Nanotech

63

Instrument: Supra 40VP SEM Magnification: 700X

"On the shoulders of giants" Description:

Carbon 3D structures

20 µm ⊢——] EHT = 5.00 kV WD = 7.1 mm

Signal A = SE2 Mag = 676 X

SE2 Stag ′6 X Wid

Stage at T = 37.1 ° Width = 443.8 μm

64

Date :10 Jun 2015 Time :23:22:39

Submitted by: Gaetano Panagia Affiliation: DTU, Nanotech Instrument: Supra 40VP SEM Magnification: 676X

"Building the world on microchip"



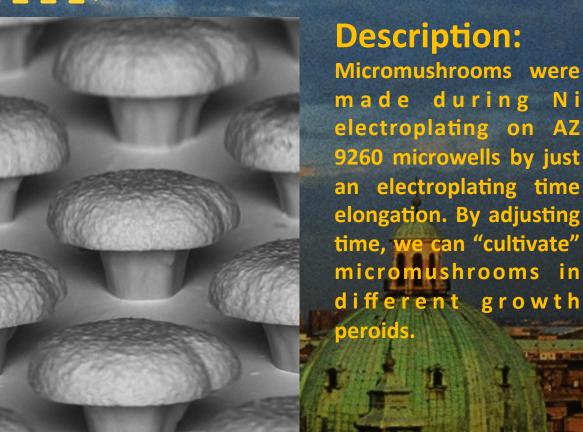
Description:

"Nothing is lost, noting is created, everything is transformed" A. Lavoisier

Submitted by: Julie FoncyInstrument: Silicon waferAffiliation: LAAS-CNRS (France)Magnification:

65

"Micromushrooms"



50 µm

Nanoflux0781

2016/02/24

NE

D14.7 x1.8k

66

Submitted by: Xiaolong TuInstrument:HITACHI TM3030SEMAffiliation: École Normale SupérieureMagnification: X 1.8k

"Lonesome nomad"

Description:

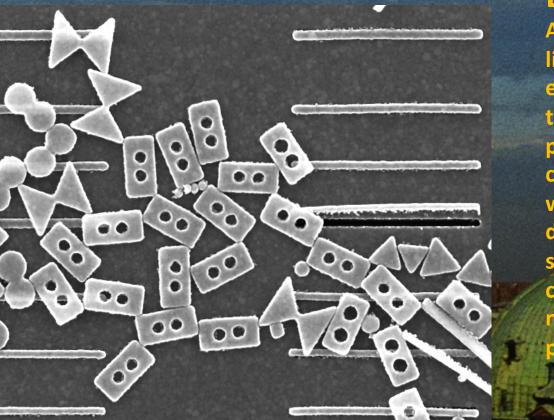
With the lack of adhesion layers a sputtered tungsten film delaminated from the substrate creating this desert-like landscape. The sample was cleaved and imaged close to grazing incidence. The debris from the sample SEM preparation resulted in this lonesome nomad looking for his next bright idea to become nanorich and microfamous!

Submitted by: Valentin Flauraud & Benoit Desbiolles Affiliation: EPFL LMIS1 Switzerland

67

Instrument: Zeiss Merlin Magnification: 1200 X





68

Description:

After electron beam lithography and evaporation of gold, the last lift-off processing step went catastrophically wrong with the delamination of most structures bringing chaos into the nanoworld of plasmonic antennas!

Submitted by: Valentin Flauraud Affiliation: EPFL LMIS1 Switzerland Instrument: Zeiss Merlin Magnification: 32'000 X

"Nanochick"

Description:

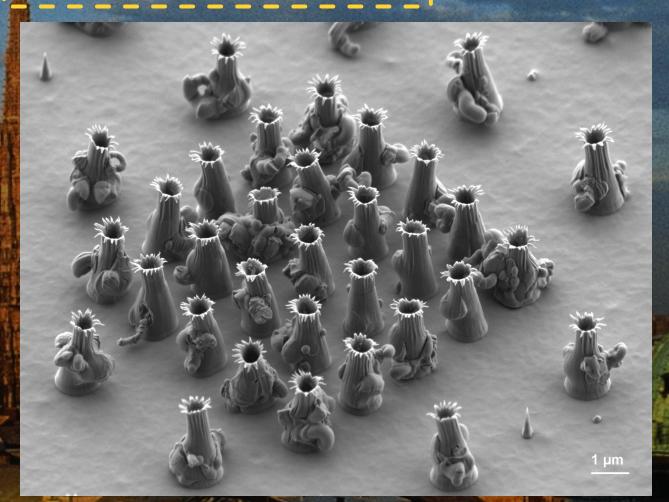
With the lack of adhesion layers a sputtered tungsten film delaminated from the substrate creating this desert-like landscape. The sample was cleaved and imaged close to grazing incidence. The debris from the sample SEM preparation resulted in this nanochick looking for some nanoseeds!

Submitted by: Valentin Flauraud & Benoit Desbiolles Affiliation: EPFL LMIS1 Switzerland

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Instrument: Zeiss Merlin Magnification: 800 X

"Sunflower party"



Description:

Metallic nano-flowers generated by IBE and **RIE of an Al-Ti-Au-Ti** coated wafer, patterned with standard photolithography. After etching, the resist is removed, the stress in the fences is released leading to the formation of the wavy stem/leaves of the flower.

Submitted by: Valentin Flauraud & Benoit Desbiolles Affiliation: EPFL LMIS1 Switzerland

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Instrument: Zeiss Merlin Magnification: 7000 X

"Silicon Light"

Description: Silicon surface after isotropic reactive ion

etching.

Submitted by: Tom Larsen Affiliation: ANEMS - EPFL

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Instrument: Carl Zeiss SEM

72 "Fluorescent Crater"

Description:

Dried salt solution with fluorescent nano-particles.

100 µm



Instrument: Optical Microscope Magnification: 10x



Description:

Nickel Corals formed when exposing Nickel to high power oxygen plasma.

Submitted by: Tom Larsen Affiliation: ANEMS - EPFL

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Instrument: Carl Zeiss SEM

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⁷⁴ "Playing the Strings"

Description:

Buckling of clampedclamped Nickel beams due to the heating by a red laser

Submitted by: Tom Larsen Affiliation: ANEMS - EPFL Instrument: Carl Zeiss SEM Magnification: 10x